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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**In re application of:
Vincent S. CHANG, et al.**

Serial No.: 10/758,317

Filed: January 15, 2004

For: HIGH TEMPERATURE HYDROGEN
ANNEALING OF A GATE INSULATOR
TO INCREASE ETCHING SELECTIVITY
BETWEEN CONDUCTIVE GATE
STRUCTURE AND GATE INSULATOR
LAYER

Group Art Unit: 1765

Examiner: Duy Vu Nguyen Deo

Commissioner for Patents
Mail Stop Amendment
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Sir:

In response to the Office Action mailed September 26, 2005, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 7 of this paper.